

# Digital Integrated Circuit (IC) Layout and Design - Lecture 4

- **FIRST LAB this Friday Jan. 20 (tomorrow)**
- 2 Lab sections
  - M 2:10pm – 5pm ENGR2 128
  - F 11:10am – 2pm ENGR2 128

<http://www.ee.ucr.edu/~rlake/EE134.html>

## Reading and Prelab

- **Week 1**
  - Read Chapter 1 of text.
- **Week 2**
  - Read Chapter 2 of text.
- **Prelab**
  - Read insert A of text, pp. 67 - 71.
  - The lab will make more sense if you read this before lab.
  - There is nothing to turn in.

# Agenda

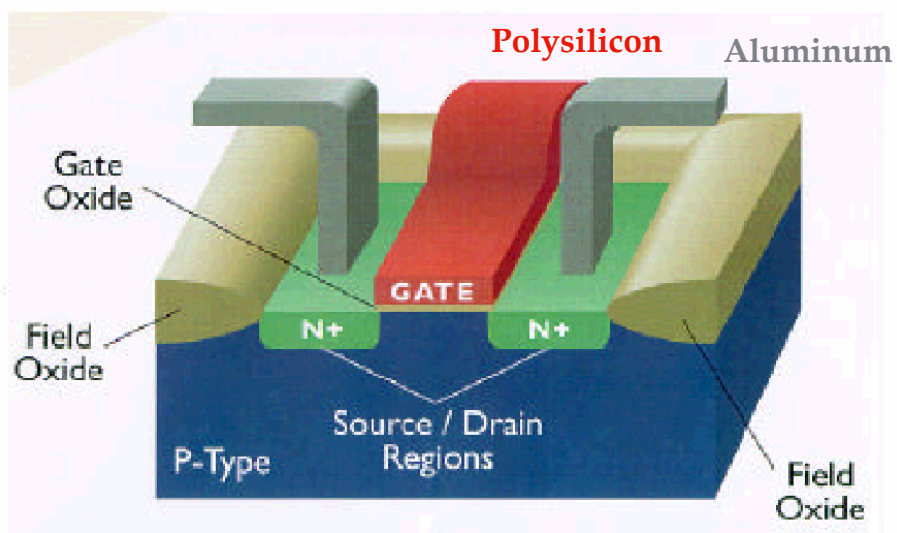
## □ Last Lecture

- MOS manufacturing process
- Design rules

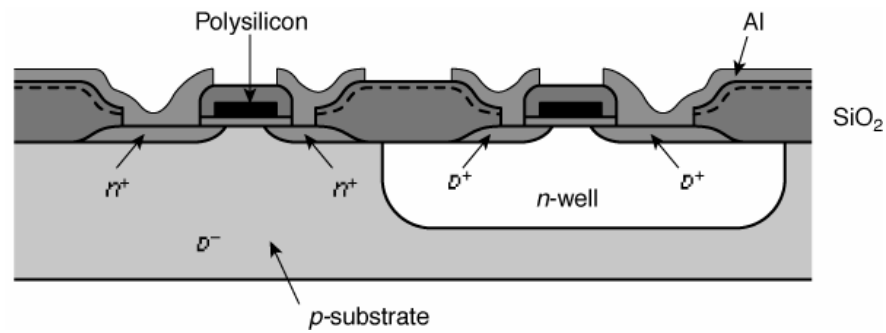
## □ Today's Lecture

- MOS manufacturing process
- Design rules
- Layout and Design
- Ties to  $V_{DD}$  and GND
- Padframes
- Pin Packages

# The MOS Transistor

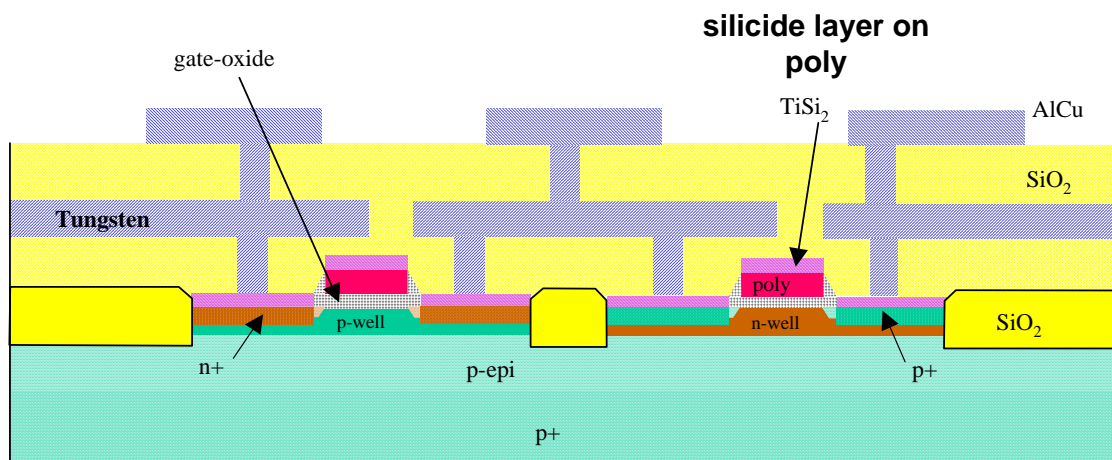


# CMOS Process



Circa 1980s

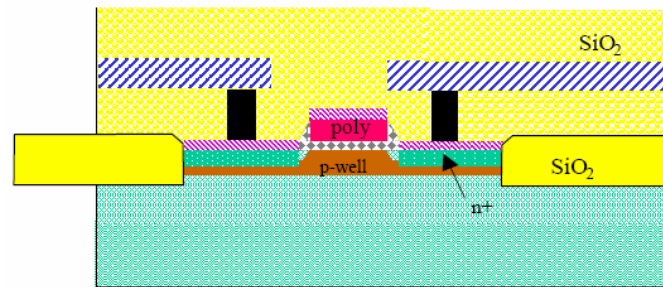
# A Modern Dual-Well CMOS Process



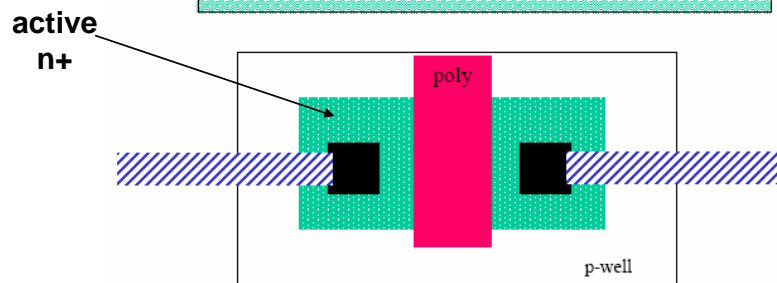
Dual-Well Trench-Isolated CMOS Process

# Transistor Layout

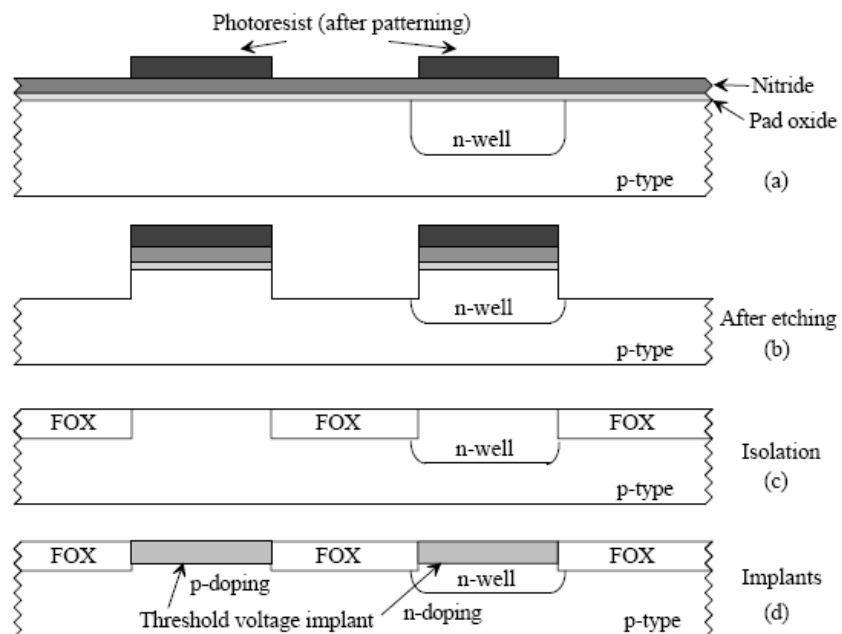
Cross-sectional view



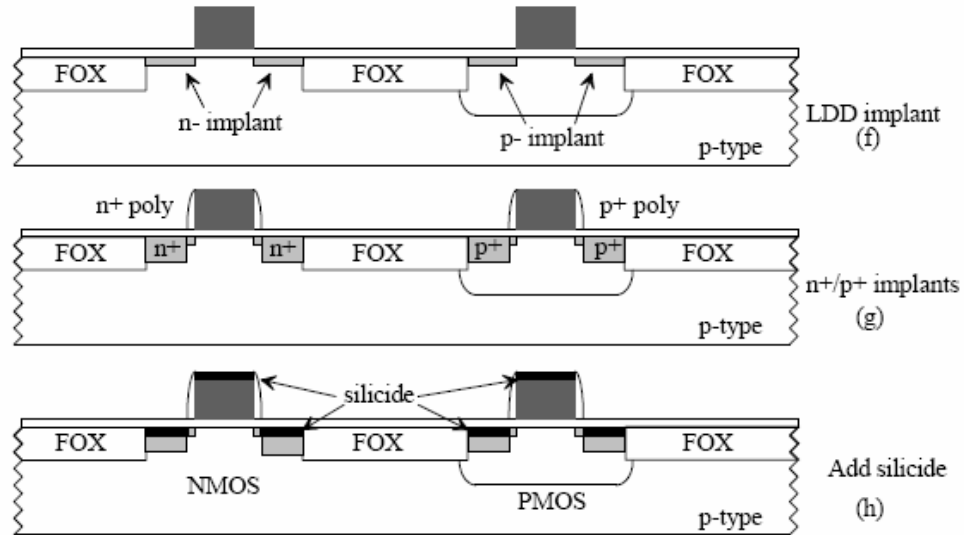
Layout view



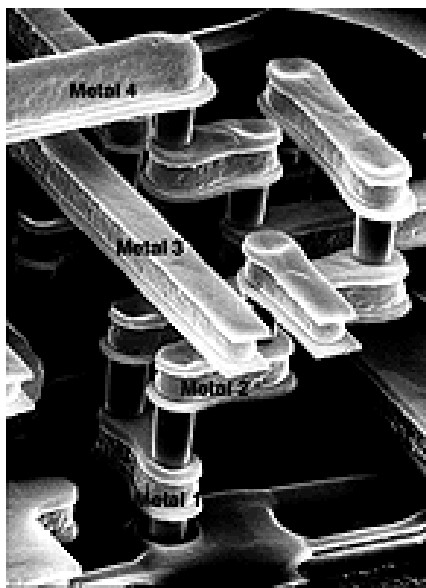
# N-Well CMOS Flow



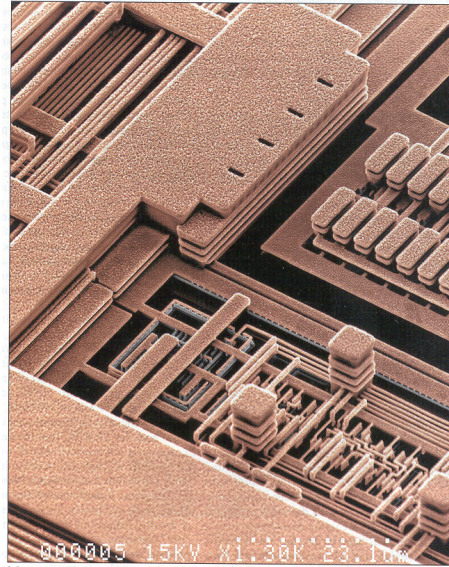
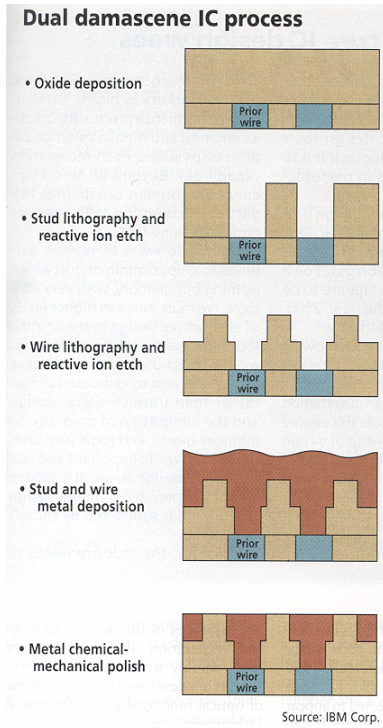
# N-Well CMOS Flow



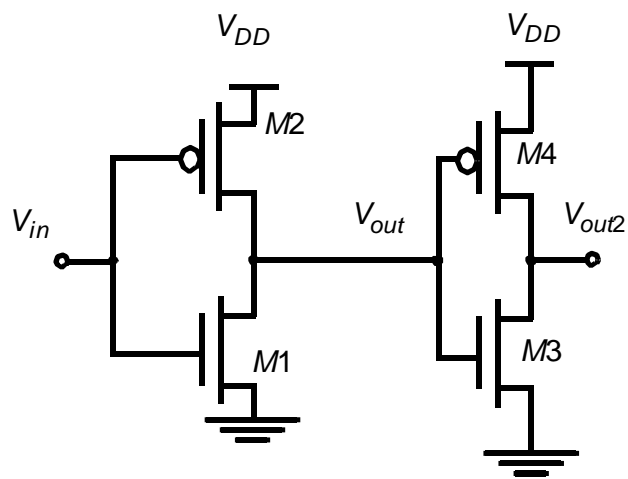
# Advanced Metallization



# Advanced Metallization

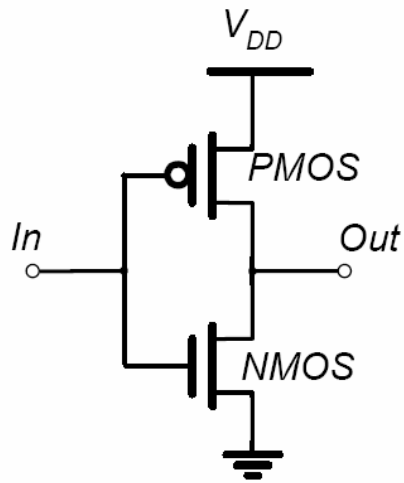


# Circuit Under Design

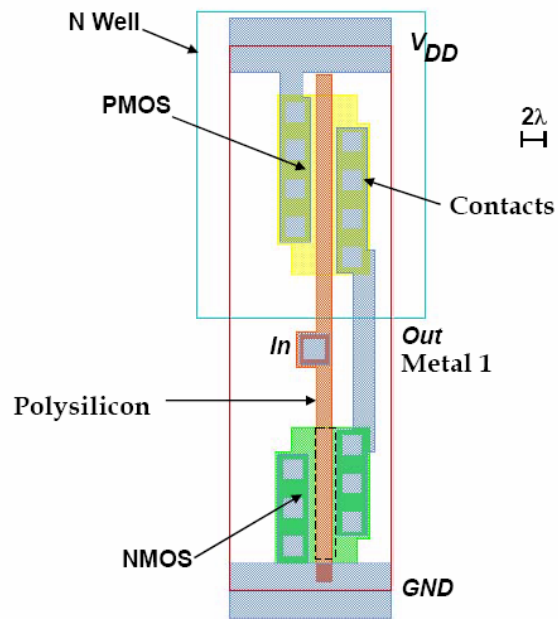


schematic

# CMOS Inverter

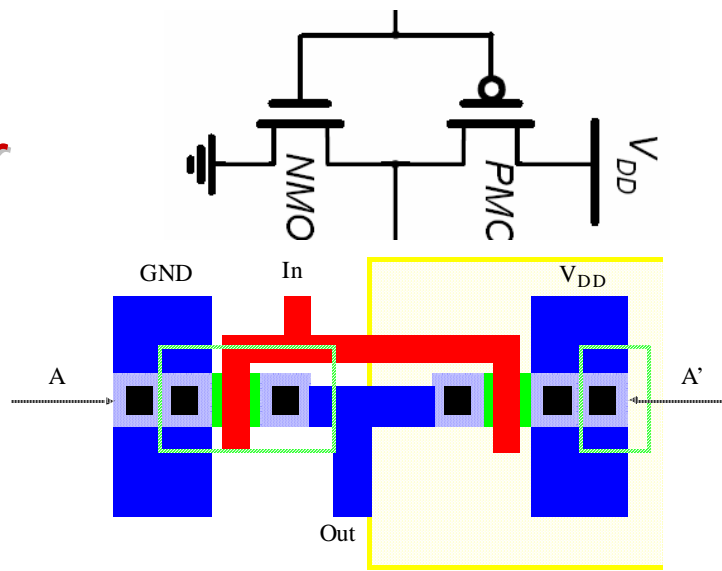


Schematic

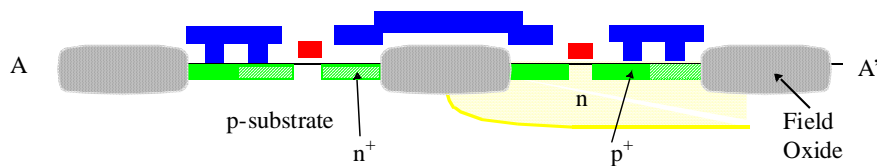


Layout

# CMOS Inverter Layout

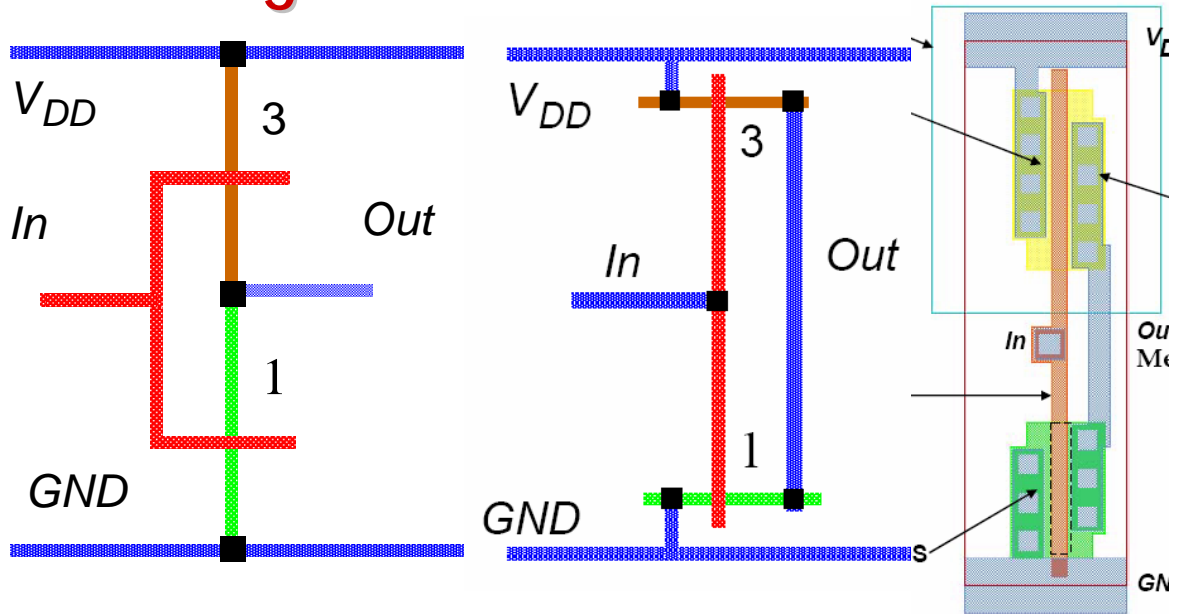


(a) Layout



(b) Cross-Section along A-A'

# Sticks Diagram

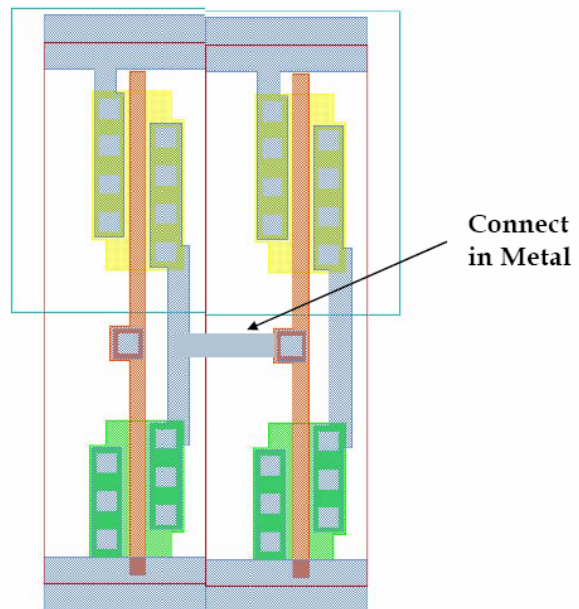
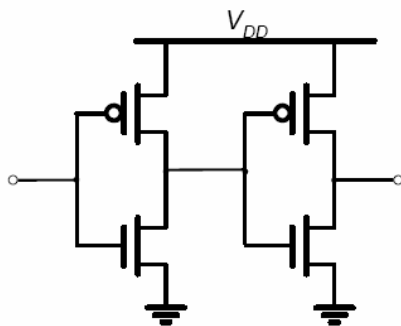


Stick diagrams of inverter

- Dimensionless layout entities
- Only topology is important

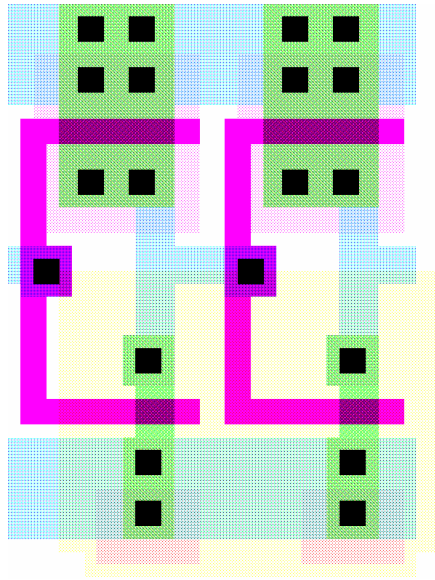
# Two Inverters

- ◆ Share power and ground
- ◆ Abut cells





# A Different Layout of Same 2 inverters












## Design Rules



















# Design Rules

- ❑ **Interface between designer and process engineer**
- ❑ **Guidelines for constructing process masks**
- ❑ **Unit dimension: Minimum line width**
  - scalable design rules: lambda parameter
    - Less common now
  - absolute dimensions (micron rules)
    - More the standard now.

# CMOS Process Layers

Layer	Color	Representation
Well (p,n)	Yellow	
Active Area (n+,p+)	Green	
Select (p+,n+)	Green	
Polysilicon	Red	
Metal1	Blue	
Metal2	Magenta	
Contact To Poly	Black	
Contact To Diffusion	Black	
Via	Black	

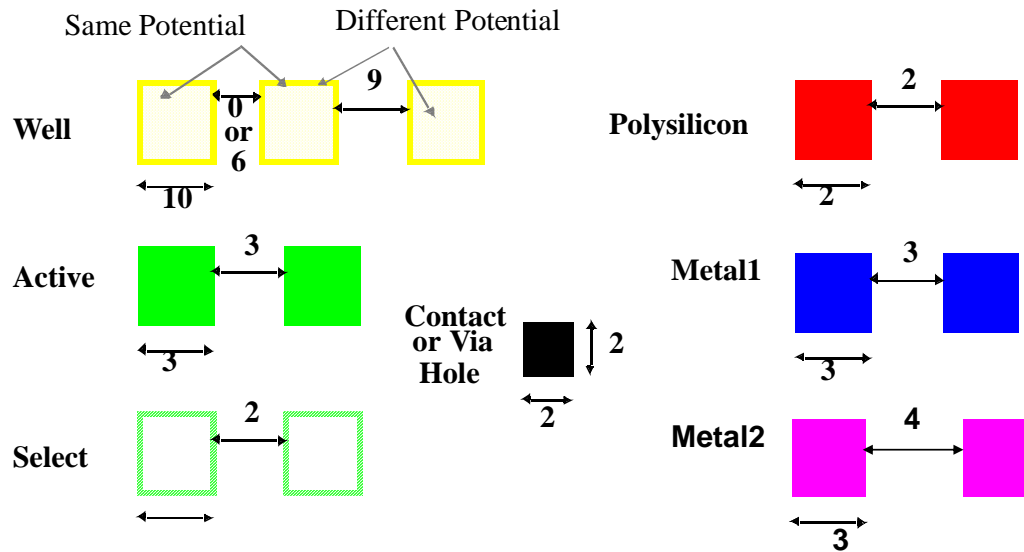
# Layers in 0.25 $\mu\text{m}$ CMOS process

Layer Description	Representation				
metal	 m1	 m2	 m3	 m4	 m5
well	 nw				
polysilicon	 poly				
contacts & vias	 ct	 v12,v23,v34,v45	 nwc	 pwc	
active area and FETs	 ndif	 pdif	 nfet	 pfet	
select	 nplus	 pplus	 prb		

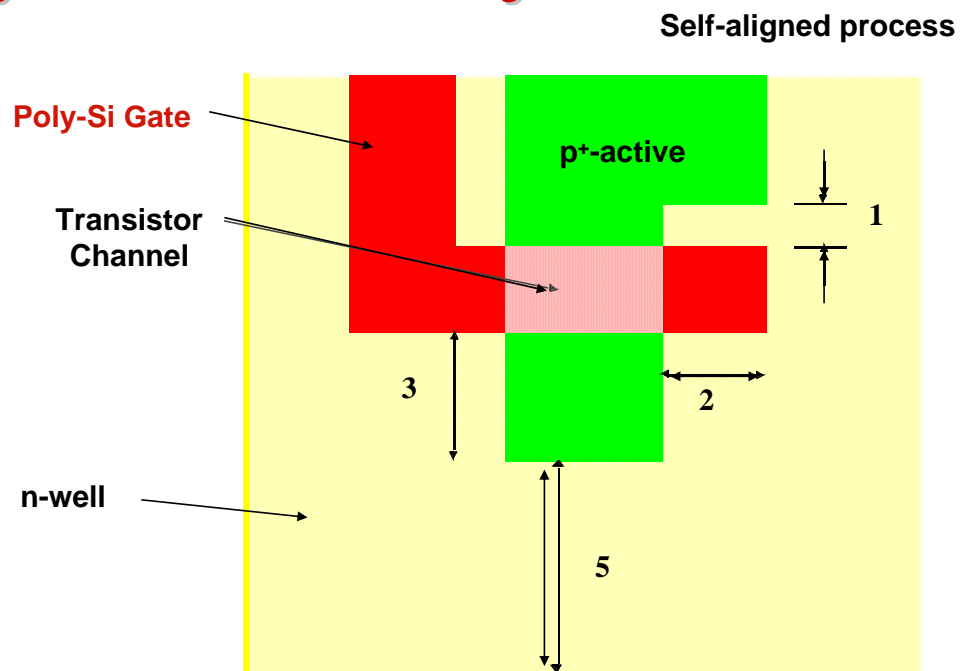
## Design Rules

- **Intra-layer: widths, spacing**
- **Inter-layer: enclosures, overlaps**
  - Transistor rules
  - Contact and via rules
  - Well and substrate contacts
- **Special rules (sub-0.25  $\mu\text{m}$ )**
  - Area, antenna rules, density rules

# Intra-Layer Design Rules



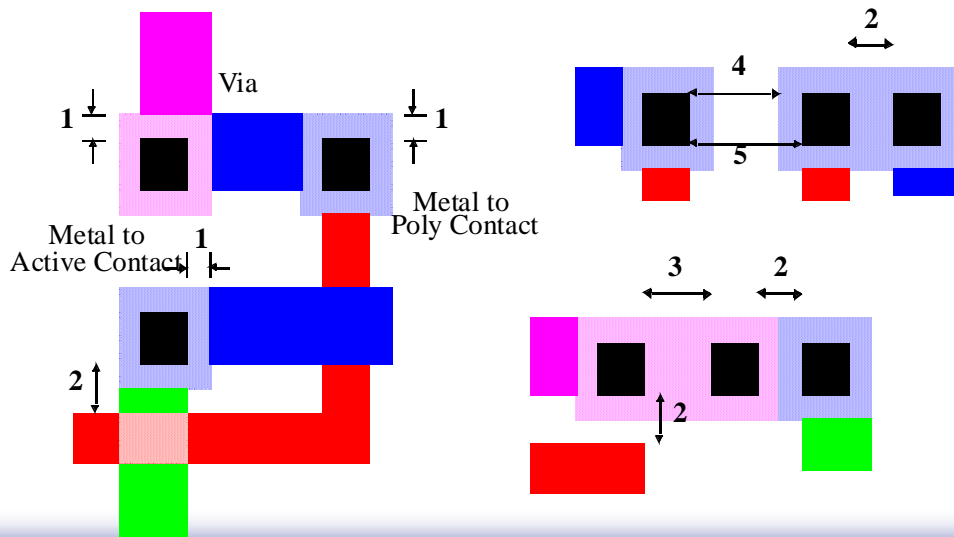
# Inter Layer: Transistor Layout



Is this an NMOS or PMOS transistor?

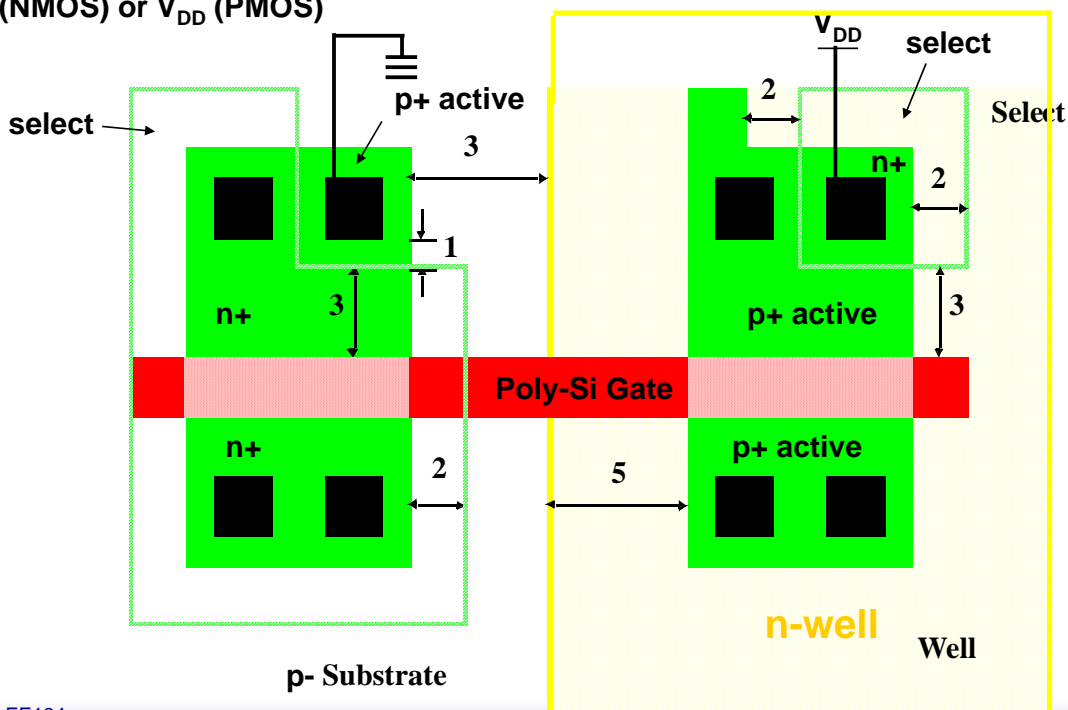
# Inter Layer: Vias and Contacts

- Vias connect metal layer 1 (M1) to metal layer 2 (M2)
- Contacts connect M1 to the Si.
- Vias and contacts are always square ( $2 \times 2 \mu\text{m}$ )
  - For large area contact, use many “contacts” in an array.



# Select Layer

Select layer reverses the sign of the doping for pinning the substrate to ground (NMOS) or  $V_{DD}$  (PMOS)

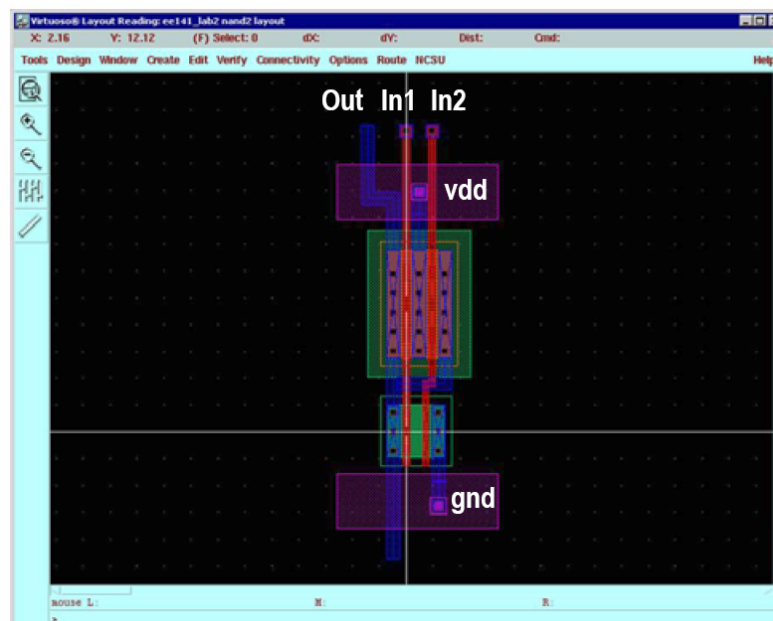


# Actual Design Rule Example (MOSIS)

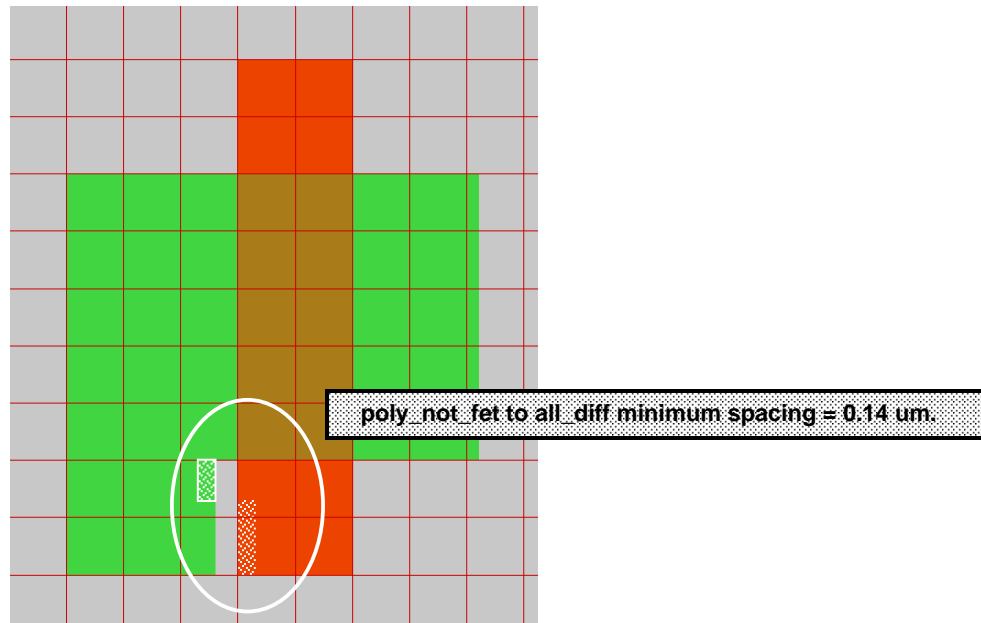
□ <http://www.mosis.org>

<http://www.mosis.org/Technical/Designrules/scmos/scmos-active.html>

# Cadence Layout Editor

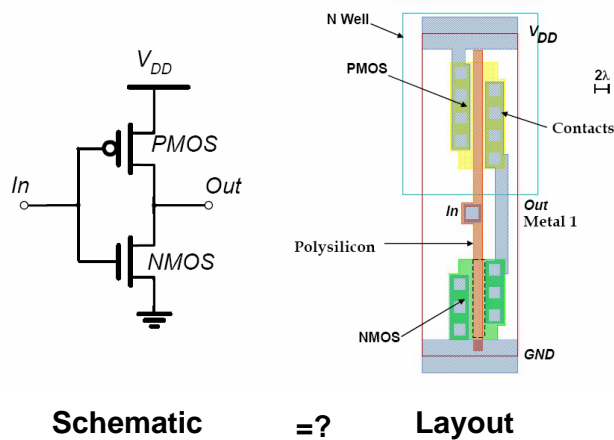


# Design Rule Checker

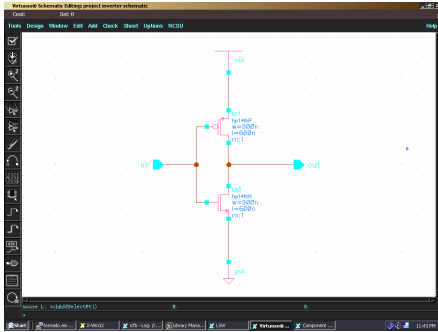


## 2 Types of Checks

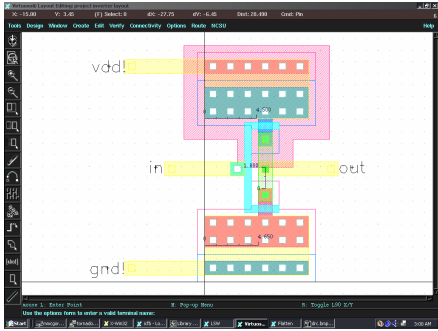
- Design Rule Checking (DRC)
- Layout vs. Schematic (LVS)



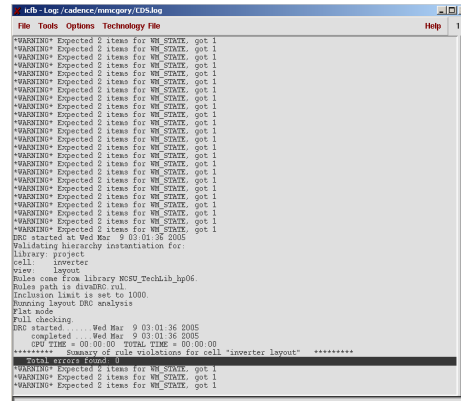
# DRC and LVS



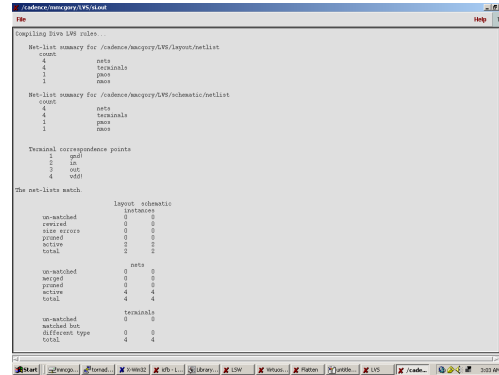
Schematic



Layout

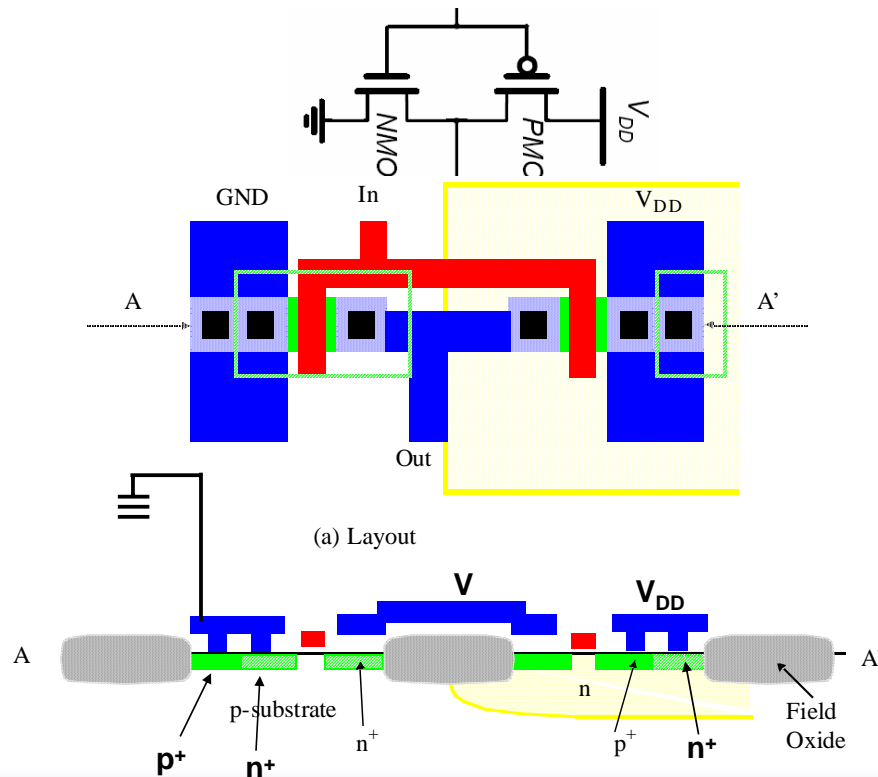


Design Rule Check



Layout vs. Schematic

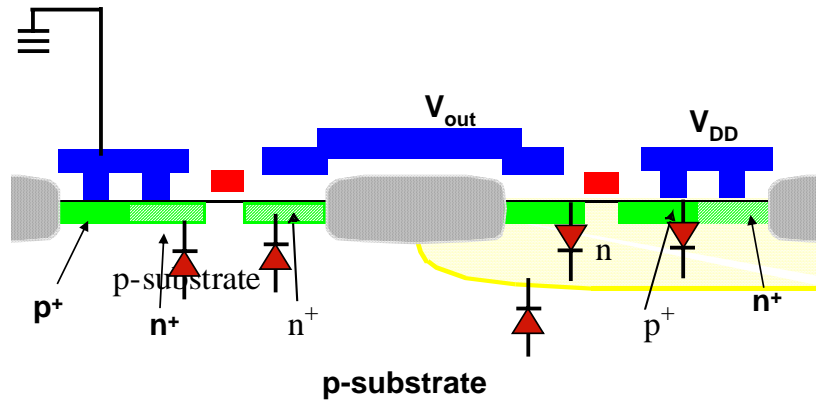
# Tie n-well to VDD and Substrate to Ground



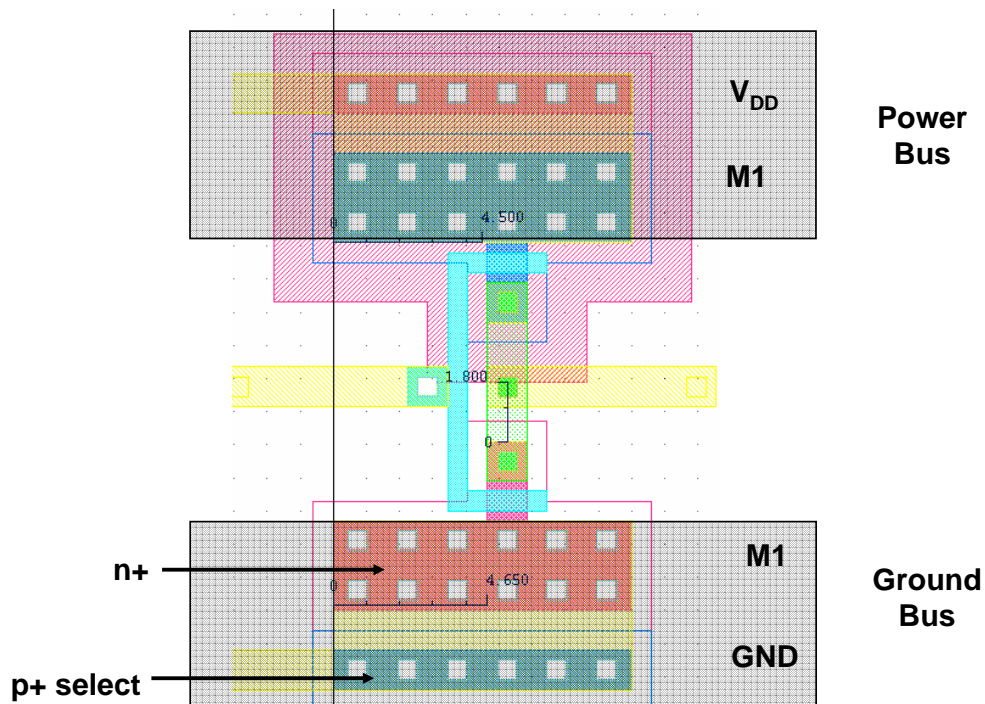


# Reason for GND and $V_{DD}$ Ties

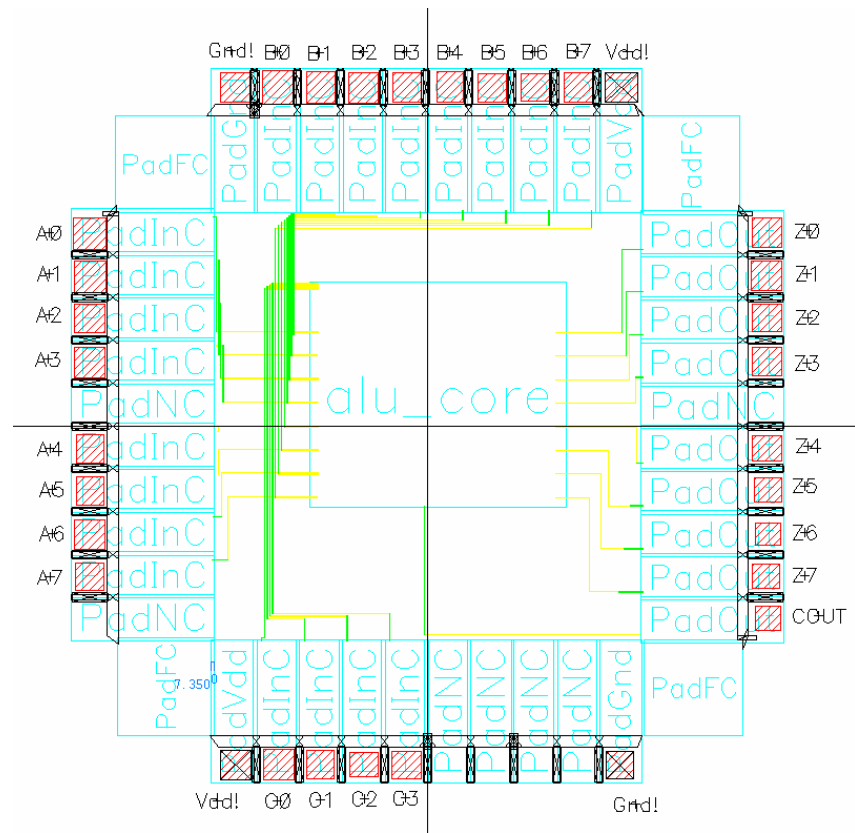
## Parasitic Diodes



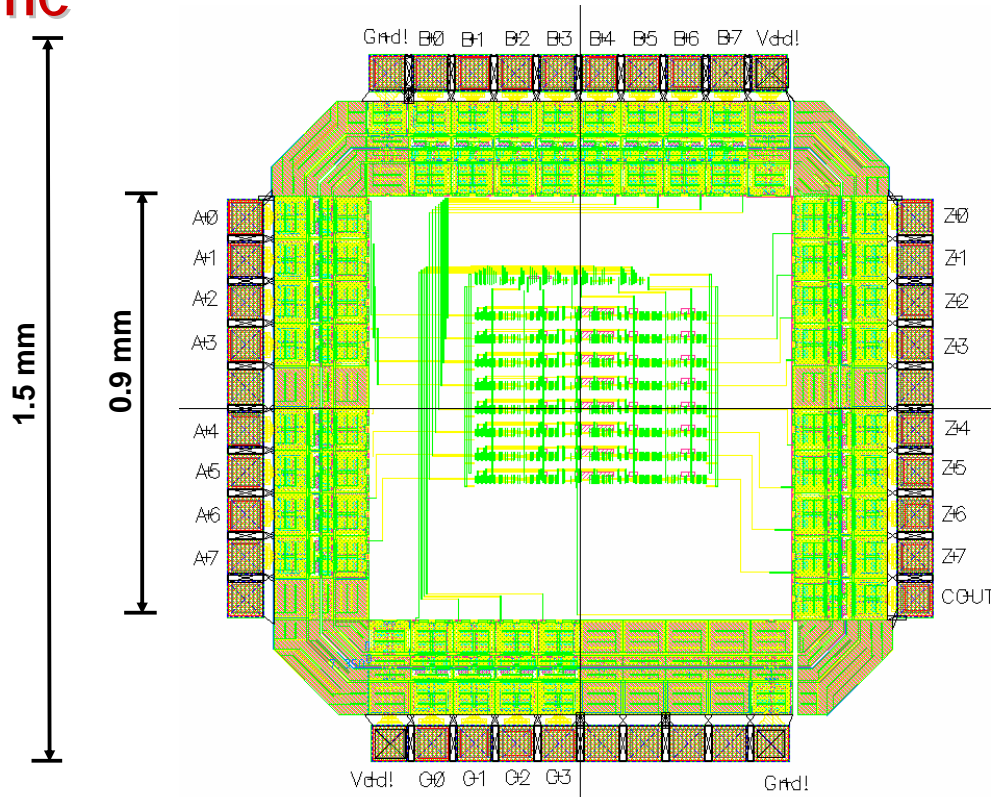
# Pin n-well to $V_{DD}$ and p-substrate to GND



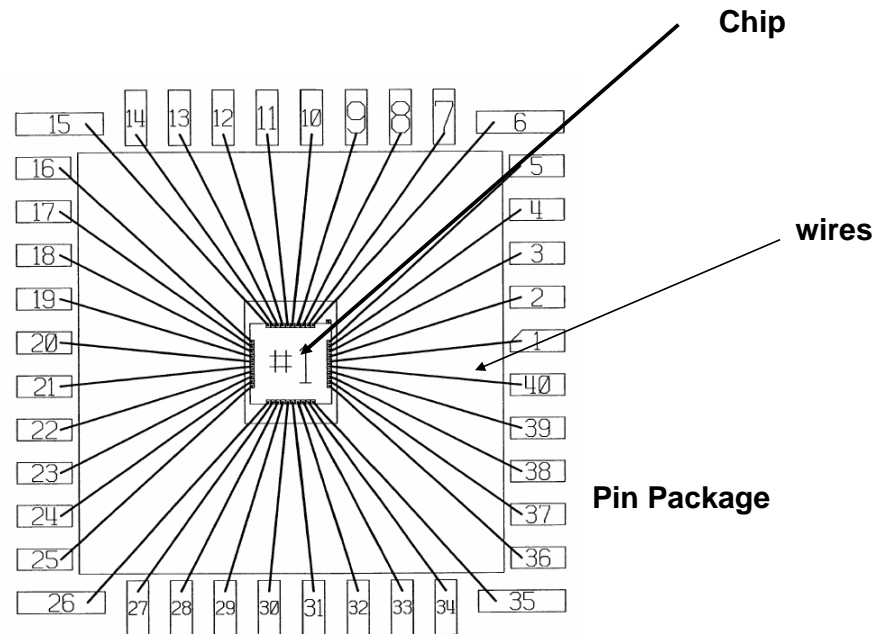
# Padframe



# Padframe



# 40 pin package



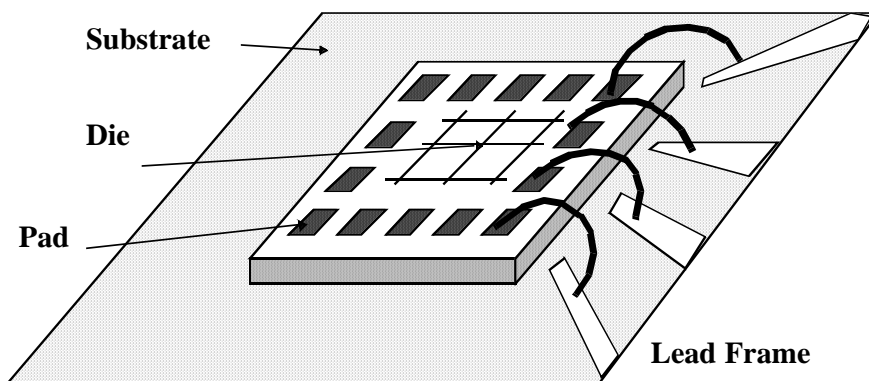
# Packaging

# Packaging Requirements

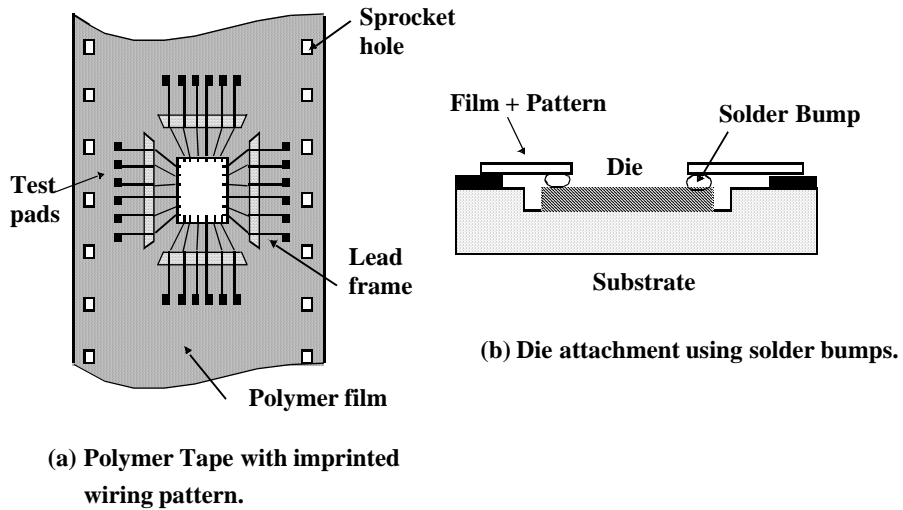
- Electrical: Low parasitics
- Mechanical: Reliable and robust
- Thermal: Efficient heat removal
- Economical: Cheap

# Bonding Techniques

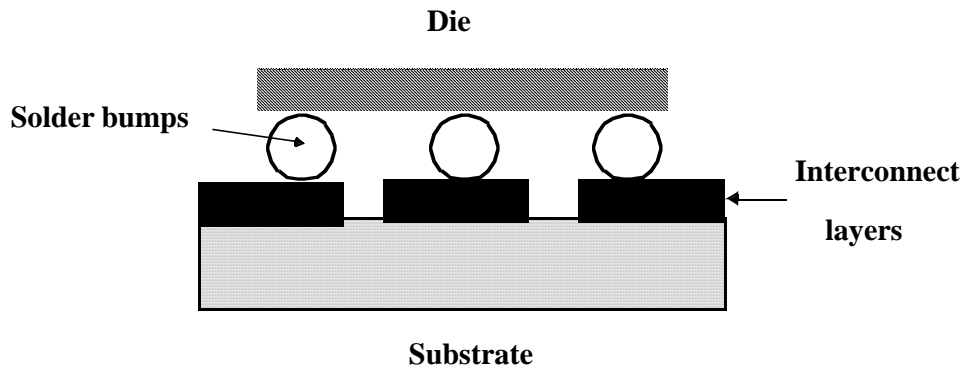
## Wire Bonding



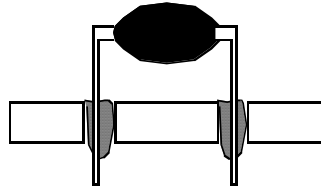
# Tape-Automated Bonding (TAB)



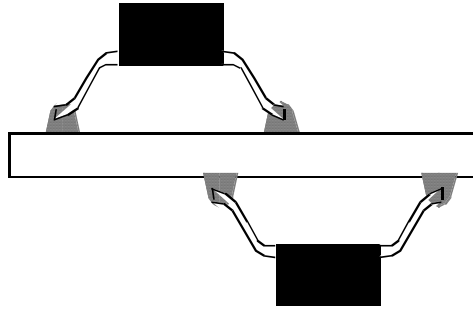
# Flip-Chip Bonding



# Package-to-Board Interconnect

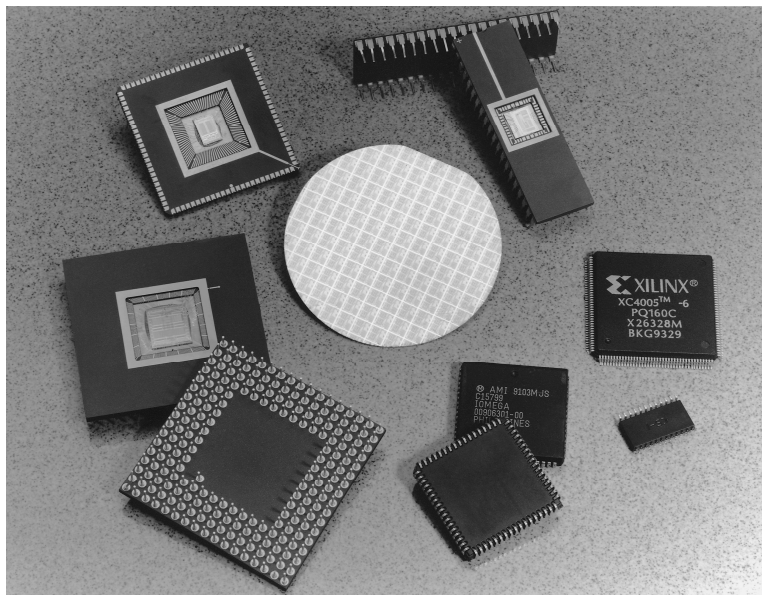


(a) Through-Hole Mounting



(b) Surface Mount

# Package Types



# Package Parameters

Package Type	Capacitance (pF)	Inductance (nH)
68 Pin Plastic DIP	4	35
68 Pin Ceramic DIP	7	20
256 Pin Pin Grid Array	5	15
Wire Bond	1	1
Solder Bump	0.5	0.1

Typical Capacitances and Inductances of Various Package and Bonding Styles (from [Sze83])

